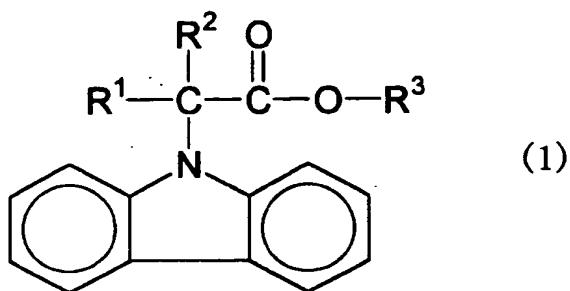


WHAT IS CLAIMED IS:

1. A carbazole derivative of the following formula (1),



5 wherein R¹ and R² individually represent a hydrogen atom or a monovalent organic group, or R¹ and R² form, together with the carbon atom to which R¹ and R² bond, a divalent organic group having a 3-8 member carbocyclic structure or a 3-8 member
10 heterocyclic structure, and R³ represents a hydrogen atom or a monovalent organic group.

2. The carbazole derivative according to claim 1, wherein the monovalent organic group represented by R¹ and R² in the
15 formula (1) is a linear, branched, or cyclic alkyl group having 1-12 carbon atoms, aromatic hydrocarbon group having 6-20 carbon atoms, oxygen-containing organic group, or nitrogen-containing organic group.

20 3. The carbazole derivative according to claim 1, wherein

the monovalent organic group represented by R^1 and R^2 in the formula (1) is a hydrogen atom, methyl group, ethyl group, n-propyl group, i-propyl group, n-butyl group, 2-methylpropyl group, 1-methylpropyl group, t-butyl group, phenyl group, or benzyl group, or a divalent organic group having an alicyclic ring formed by R^1 , R^2 , and the carbon atom to which R^1 and R^2 bond, which is derived from cyclohexane.

4. The carbazole derivative according to claim 1, wherein the monovalent organic group represented by R^3 in the formula (1) is a linear, branched, or cyclic alkyl group having 1-12 carbon atoms, aromatic hydrocarbon group having 6-20 carbon atoms, oxygen-containing organic group, nitrogen-containing organic group, or acid-dissociable organic group.

5. The carbazole derivative according to claim 1, wherein the monovalent organic group represented by R^3 in the formula (1) is a hydrogen atom, methyl group, ethyl group, n-propyl group, n-butyl group, 2-methylpropyl group, or phenyl group, or an acid-dissociable organic groups selected from the group consisting of an i-propyl group, 1-methylpropyl group, t-butyl group, cyclohexyl group, benzyl group, t-butoxycarbonylmethyl group, 1-methoxyethyl group, 1-ethoxyethyl group, trimethylsilyl group, t-butoxycarbonyl group, tetrahydrofuranyl group, tetrahydropyranyl group, tetrahydrothiofuranyl group, and tetrahydrothiopyranyl group.

6. The carbazole derivative according to claim 1, wherein R^3 in the formula (1) is an i-propyl group, t-butyl group, cyclohexyl group, or benzyl group.

5 7. The carbazole derivative according to claim 1, wherein R^1 and R^2 in the formula (1) are hydrogen atoms.

10 8. The carbazole derivative according to claim 1, wherein R^3 in the formula (1) is an acid-dissociable organic group.

9. A chemically amplified radiation-sensitive resin composition comprising the carbazole derivative of claim 1.

15 10. A positive tone radiation-sensitive resin composition comprising (A) the carbazole derivative of claim 1, (B) an acid-dissociable group-containing resin which is insoluble or scarcely soluble in alkali, but becomes alkali soluble when the acid-dissociable group dissociates, and (C) a photoacid generator.

20 11. The chemically amplified radiation-sensitive resin composition according to claim 10, comprising the carbazole derivative (A) in an amount of 0.1-40 parts by weight for 100 parts by weight of the acid-dissociable group-containing resin
25 (B).

12. The chemically amplified radiation-sensitive resin

composition according to claim 10, wherein the acid-dissociable group-containing resin (B) is a resin obtainable from a poly(p-hydroxystyrene), a copolymer of p-hydroxystyrene and p-hydroxy- α -methylstyrene, a copolymer of p-hydroxystyrene and styrene, or a copolymer of p-hydroxystyrene and/or p-hydroxy- α -methylstyrene and (meth)acrylic acid by replacing a part or all of the hydrogen atoms in the phenolic hydroxyl groups or the hydrogen atoms in the carboxylic groups with an acid-dissociable group.

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13. The chemically amplified radiation-sensitive resin composition according to claim 10, wherein the acid-dissociable group is a substituted methyl group, 1-substituted ethyl group, 1-branched alkyl group, silyl group, germyl group, alkoxy carbonyl group, acyl group, or cyclic acid-decomposable group.

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14. The radiation-sensitive resin composition according to claim 10, wherein the amount of the acid-dissociable groups introduced into the acid-dissociable group-containing resin (B) is 15-100%.

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15. The radiation-sensitive resin composition according to claim 10, wherein the photoacid generator (C) is at least one compound selected from the group consisting of onium salt compounds, sulfone compounds, sulfonate compounds, sulfonimide compounds, disulfonyldiazomethane compounds,

disulfonylmethane compounds, oximesulfonate compounds, and hydrazine sulfonate compounds.

16. The chemically amplified radiation-sensitive resin
5 composition according to claim 10, comprising the photoacid generator (C) in an amount of 0.1-20 parts by weight for 100 parts by weight of the acid-dissociable group-containing resin (B).

10 17. The chemically amplified radiation-sensitive resin composition according to claim 10, further comprising an acid diffusion controller.

15 18. The chemically amplified radiation-sensitive resin composition according to claim 17, wherein the acid diffusion controller is a nitrogen-containing organic compound.